	Application No.	Applicant(s)
Notice of Allowability	10/711,300	VOLDMAN ET AL.
	Examiner	Art Unit
	Walter L. Lindsay, Jr.	2812
The MAILING DATE of this communication apperall claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in to or other appropriate community GHTS. This application is sufficient to the community of the communi	his application. If not included ication will be mailed in due course. <b>THIS</b>
1. This communication is responsive to An amendment filed	<u>4/25/2005</u> .	•
2. The allowed claim(s) is/are 1,2 and 4-12.		
3. The drawings filed on <u>09 September 2004</u> are accepted by	the Examiner.	
<ul> <li>4. Acknowledgment is made of a claim for foreign priority unally all b) Some* c) None of the: <ol> <li>Certified copies of the priority documents have</li> <li>Certified copies of the priority documents have</li> <li>Copies of the certified copies of the priority documents have</li> <li>International Bureau (PCT Rule 17.2(a)).</li> </ol> </li> <li>* Certified copies not received: <ol> <li>Applicant has THREE MONTHS FROM THE "MAILING DATE" on the priority documents have</li> </ol> </li> <li>Applicant has THREE MONTHS FROM THE "MAILING DATE" on the priority documents have</li> <li>THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.</li> </ul>	been received. been received in Application cuments have been received in the communication to file a	No n this national stage application from the
5. A SUBSTITUTE OATH OR DECLARATION must be submit informal patent application (PTO-152) which give		
6. CORRECTED DRAWINGS (as "replacement sheets") mus	t be submitted.	
(a) including changes required by the Notice of Draftspers	on's Patent Drawing Review (	PTO-948) attached
1)  hereto or 2)  to Paper No./Mail Date		
(b)  including changes required by the attached Examiner's Paper No./Mail Date	s Amenament / Comment or in	the Oπice action of
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the		
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT I	•	
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. 🔲 Interview Sum	rmal Patent Application (PTO-152) nmary (PTO-413), ail Date
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date	·	mendment/Comment
	8. 🛛 Examiner's St	eatement of Reasons for Allowance
	MICH	AEL LEBENTRITT ORY PATENT EXAMINER

Art Unit: 2812

## **DETAILED ACTION**

This Office Action is in response to an Amendment filed on 4/25/2005.

Currently, claims 1-2, and 4-12 are pending. Claims 3, and 13-22 have been canceled.

## Allowable Subject Matter

- 1. Claims 1,2 and 4-12 are allowed.
- 2. The following is an examiner's statement of reasons for allowance: the prior art, either singly or in combination fails to anticipate or render obvious, the limitations of:

...a heavily doped region of said second polarity abutting said trench structure; and

a shallow trench isolation region, wherein said trench structure comprises a deep trench structure having a depth and a width, wherein said depth is at least twice as large as said width, and wherein said shallow trench isolation region is over said deep trench structure,

wherein said heavily doped region having a dopant concentration greater than a dopant concentration of said well region, and wherein said heavily doped region is adapted to suppress latch-up in said integrated circuit, as required by claim 1; and

...p-type diffusion regions in said p-type substrate and in between successive ones of said STI regions;

a n-type retrograde well in said p-type substrate;

a deep trench isolation region bounding said p-type diffusion regions and said n-type retrograde well; and

Application/Control Number: 10/711,300

Art Unit: 2812

a n-type sub-collector adjacent to a sidewall of said deep trench isolation region and below said STI regions,

wherein said p-type diffusion regions, said n-type retrograde well, and said p-type substrate from a pnp parasitic bipolar transistor in said CMOS device, and

wherein said deep trench isolation region and said n-type sub-collector are adapted to suppress latch-up in said CMOS device that is caused by said pnp parasitic bipolar transistor, as required by claim 8.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Walter L. Lindsay, Jr. whose telephone number is (571) 272-1674. The examiner can normally be reached on Monday-Thursday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael S. Lebentritt can be reached on (571) 272-1873. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Art Unit: 2812

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

May 4 2005

MICHAEL LEBENTRITT
SUPERVISORY PATENT EXAMINITY